

by hydroperoxides, through reactions using metalloporphyrins, to the very important area of oxidations on zeolites.

This book is clearly produced, with relatively few typographic errors, and clear diagrams. The index is good, and each chapter is accompanied by extensive references, running well into 1988. Each chapter has been written by an expert in the area, and is of high quality. I would have liked to see somewhat more material from industrial contributors. Overall this is an excellent book, which should be bought by all chemistry libraries, and by any individual actively working in the field.

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Molecular Structure of Organosilicon Compounds; by E. Lukevics, O. Pudova, and R. Sturkovich, Ellis Horwood, Chichester, 1989, 359 pages, £69.95. ISBN 0-7458-0692-9.

This book is in the main an English translation of the Russian version that was published in 1988 and very favourably reviewed in this journal by L. Haiduc (*J. Organomet. Chem.*, 375 (1989) C43). Some new material, including details of 200 new structures, has been added to take account of relevant publications that appeared after the original version was written.

There is little to add to Professor Haiduc's review. The book presents a very useful survey of structures of organosilicon compounds as determined by microwave and electron and X-ray diffraction methods. From the nature of the subject it is essentially a factual presentation of information, but unusual features are commented on where appropriate. The material is organized under the following chapter headings: (1) Organosilanes (organosilicon hydrides, tetraorganosilanes, silacyclic compounds, and silaethylenes); (2) Polysilanes; (3) Organometallic and organometalloid derivatives of silicon (oddly in view of its title, this chapter, though mainly devoted to compounds with bond between Si and metals or metalloids also deals with bonds to elements of Groups V–VII such as O, N, and halogens); (4) Compounds containing penta- and hexa-coordinate silicon. There are 1660 references in the text and an 8 page list of references to relevant papers that appeared in 1987–1988. There is a formula index, but no author index.

The volume is well presented; the print is of exceptional clarity, and the structural diagrams and tables are very clear. (Very wisely compounds are depicted as line structural formulae rather than in ORTEP or similar X-ray representations.) The translation (by J. Eiduss and S. Avertsev) is into good English; the only recurrent error that I notice involves confusion of a bond and a bond length, as in "The Si–Cl bond is increased..." and "Minimum values of Si–M bonds have been found...", but this is not unknown in papers by British or American authors!

Inevitably, in view of its subject matter, the book will be used essentially as a source of detailed information, but profit can be gained from glancing through its pages to form a picture of the wide range of types of organosilicon compounds that have been studied. I am very glad to have it on my shelves, and I recommend it to

all those interested in structures of organosilicon compounds or of organometallic compounds in general.

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Colin Eaborn

Erratum

Re: Monoorganomercury and diorganothallium derivatives of 2-thiouracil and 2-S-methylthiouracil; crystal structure of methylmercury(II)-2-S-methylthiouracilate; by M.S. García Tasende, M.I. Suárez Gimeno, A. Sánchez, J.S. Casas, J. Sordo and E.E. Castellano (*J. Organomet. Chem.*, 384 (1990) 19–32).

p. 29, line 2 should read:

H ₂ Tu	176.3	161.3	142.3	105.4
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